

L Number	Hits	Search Text	DB	Time stamp
-	457	(257/(E21.53)).CCLS.	USPAT; US-PGPUB	2003/05/21 10:12
-	567	(438/16).CCLS.	USPAT; US-PGPUB	2003/05/21 10:13
-	1380	(438/FOR.142).CCLS.	EPO; JPO; DERWENT	2003/05/22 17:08
-	26	((257/(E21.53)).CCLS.) and grating	USPAT; US-PGPUB	2003/05/21 12:22
-	43	((438/16).CCLS.) and grating	USPAT; US-PGPUB	2003/05/21 13:53
-	6	("4600597" "5393624" "5867276" "5880838" "6051348" "6245584").PN.	USPAT	2003/05/21 13:31
-	168	(438/FOR.101).CCLS.	EPO; JPO; DERWENT	2003/05/21 14:07
-	1	((438/FOR.101).CCLS.) and grating	EPO; JPO; DERWENT	2003/05/21 13:55
-	601	(CD or "critical dimension") same grating	USPAT; US-PGPUB	2003/05/21 14:46
-	43	((CD or "critical dimension") same grating) and (STI or trench)	USPAT; US-PGPUB	2003/05/21 15:18
-	4	("5867276" "5877276" "5880838" "6245584").PN.	USPAT	2003/05/21 15:17
-	57	((CD or "critical dimension") same grating) and (CMP or polishing or "chemical mechanical")	USPAT; US-PGPUB	2003/05/21 15:19
-	1	"09/714,984"	USPAT; US-PGPUB	2003/05/21 17:50
-	742	(CD or ((lateral or width or critical) adj dimension)) same (CMP or "chemical mechanical" or polishing)	USPAT; US-PGPUB	2003/05/21 18:01
-	17	((CD or ((lateral or width or critical) adj dimension)) same (CMP or "chemical mechanical" or polishing)) same parameter	USPAT; US-PGPUB	2003/05/21 18:01
-	184	((CD or ((lateral or width or critical) adj dimension)) same (STI or "shallow trench"))	USPAT; US-PGPUB	2003/05/21 18:07
-	5	((CD or ((lateral or width or critical) adj dimension)) same (STI or "shallow trench")) same height	USPAT; US-PGPUB	2003/05/21 18:05
-	6	(CD or ((lateral or width or critical) adj dimension)) and ((STI or "shallow trench") same ("step height"))	USPAT; US-PGPUB	2003/05/21 18:09
-	0	(recipe same (CMP or polishing or "chemical mechanical")) and (((lateral or width or critical) near3 (dimension or uniformity or error or bias or tolerance or variation)) or CD) with (reflectiv\$3 or intensity)	USPAT; US-PGPUB	2003/05/22 10:26
-	262	recipe same (CMP or polishing or "chemical mechanical")	USPAT; US-PGPUB	2003/05/22 10:26
-	37	(recipe same (CMP or polishing or "chemical mechanical")) and (((lateral or width or critical) near3 (dimension or uniformity or error or bias or tolerance or variation)) or CD)	USPAT; US-PGPUB	2003/05/22 18:24
-	155	(STI or "trench isolation" or "trench region" or "isolation region") with (((lateral or width or critical) near3 (dimension or uniformity or error or bias or tolerance or variation)) or CD)	USPAT; US-PGPUB	2003/05/22 13:29
-	0	(diffraction or diffracting) same (reflectiv\$4) same (STI or "trench isolation") same (height)	USPAT; US-PGPUB	2003/05/22 13:19
-	3	(diffraction or diffracting or reflectiv\$4) same (STI or "trench isolation") same (height)	USPAT; US-PGPUB	2003/05/22 13:20
-	8	(diffraction or diffracting or reflectiv\$4) same (STI or "trench isolation") same planariz\$5	USPAT; US-PGPUB	2003/05/22 13:20

-	4	((topography or "step height") same ((width or line) with variation) same ("isolation region" or STI or "trench isolation"))	USPAT; US-PGPUB	2003/05/22 18:16
-	10	((topography or "step height") same ((width or line) with variation))and ("isolation region" or STI or "trench isolation"))	USPAT; US-PGPUB	2003/05/22 17:05
-	1380	((438/FOR.142).ccls.)	EPO; JPO; DERWENT	2003/05/22 17:08
-	0	((438/FOR.142).ccls.) and sti	EPO; JPO; DERWENT	2003/05/22 17:09
-	4	((438/FOR.142).ccls.) and trench	EPO; JPO; DERWENT	2003/05/22 17:09
-	0	((((438/FOR.142).ccls.)) and "step height"	EPO; JPO; DERWENT	2003/05/22 17:10
-	1	(((438/FOR.142).ccls.)) and ((line or width) with variation)	EPO; JPO; DERWENT	2003/05/22 17:10
-	3	(((438/FOR.142).ccls.)) and (CD or "critical dimension" or "lateral dimension")	EPO; JPO; DERWENT	2003/05/22 18:14
-	465	(topography or "step height") same ("isolation region" or STI or "trench isolation"))	USPAT; US-PGPUB	2003/05/22 18:17
-	436	((topography or "step height") same ("isolation region" or STI or "trench isolation")) and (gate or electrode or polysilicon or poly or line)	USPAT; US-PGPUB	2003/05/22 18:18
-	2	((((topography or "step height") same ("isolation region" or STI or "trench isolation")) and (gate or electrode or polysilicon or poly or line)) and (metrology or scatterom\$5)	USPAT; US-PGPUB	2003/05/22 18:19
-	1331	(CMP or polish\$3 or "chemical mechanical") same (((lateral or width or critical) near3 (dimension or uniformity or error or bias or tolerance or variation)) or CD)	USPAT; US-PGPUB	2003/05/22 18:25
-	889	(CMP or polish\$3 or "chemical mechanical") same (((lateral or width or critical) near3 (dimension or uniformity or error or bias or tolerance or variation)))	USPAT; US-PGPUB	2003/05/22 18:26
-	174	(438/32).CCLS.	USPAT; US-PGPUB	2003/05/22 18:31
-	33	(CMP or polish\$3 or "chemical mechanical") and (profile same (compar\$3 or measur\$3 or match\$3)) and ((CD or "critical dimension") with (variation or variance)) and planariz\$6	USPAT; US-PGPUB	2003/05/23 07:15
-	1368	(polish\$3) with (STI or trench) with oxide	USPAT; US-PGPUB	2003/05/23 07:15
-	68	((polish\$3) with (STI or trench) with oxide) and ((width or line) with (variation or variance))	USPAT; US-PGPUB	2003/05/23 07:41
-	576	((control\$4) with (polish\$3 or planariz\$5)) same (parameter or recipe)	USPAT; US-PGPUB	2003/05/23 08:06
-	68	((((control\$4) with (polish\$3 or planariz\$5)) same (parameter or recipe)) and (STI or "trench isolation" or "isolation region")	USPAT; US-PGPUB	2003/05/23 08:07
-	75	((((control\$4) with (polish\$3 or planariz\$5)) same (parameter or recipe)) and ((lateral or width or critical) near3 (dimension or uniformity or error or bias or tolerance or variation))	USPAT; US-PGPUB	2003/05/23 08:23
-	17	((((control\$4) with (polish\$3 or planariz\$5)) same (parameter or recipe)) and ((lateral or width or critical) near3 (dimension or uniformity or error or bias or tolerance or variation))) and grating	USPAT; US-PGPUB	2003/05/23 08:17

-	1	("6,054,868").PN.	USPAT; US-PGPUB	2003/05/23 08:17
-	58	((((control\$4) with (polish\$3 or planariz\$5)) same (parameter or recipe)) and ((lateral or width or critical) near3 (dimension or uniformity or error or bias or tolerance or variation))) not (((((control\$4) with (polish\$3 or planariz\$5)) same (parameter or recipe)) and ((lateral or width or critical) near3 (dimension or uniformity or error or bias or tolerance or variation))) and grating)	USPAT; US-PGPUB	2003/05/23 08:27
-	5568	(reduc\$3 or control\$5) with (CD or critical or lateral or width) with (variation or variance)	USPAT; US-PGPUB	2003/05/23 09:54
-	23	((reduc\$3 or control\$5) with (CD or critical or lateral or width) with (variation or variance)) same (CMP or polish\$3)	USPAT; US-PGPUB	2003/05/23 08:32
-	1	("6458015").PN.	USPAT; US-PGPUB	2003/05/23 08:32
-	5	("5420796" "5917332" "5971586" "5972727" "6016562").PN.	USPAT	2003/05/23 08:46
-	1372	((reduc\$3 or control\$5) with (CD or critical or lateral or width) with (variation or variance)) and feedback	USPAT; US-PGPUB	2003/05/23 09:54
-	98	((reduc\$3 or control\$5) with (CD or critical or lateral or width) with (variation or variance)) and feedback) and (cmp or polish\$3)	USPAT; US-PGPUB	2003/05/23 10:22